



# UV Ozone Cleaner



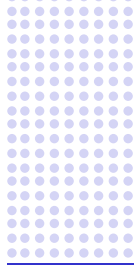
The **REVARON UV-Ozone** cleaner with Heated platform is capable of providing instantly atomic scale cleaning to obtain ultra clean substrates and surfaces by removing contamination. This is achieved with the use of UV light to generate ozone that reacts with the organic contaminants and these volatile by-products evaporate to obtain atomically clean surfaces. Importantly this is achieved without any damage to the sample or underlying thin films/coatings. This versatile instrument can treat and clean wide range of materials and substrates facilitating its use in endless applications. Most preferred by the industry and universities due to dry process that completely eliminates the use of chemicals. UV cleaning process of sample surfaces is most commonly used in material and device research.



## UV OZONE CLEANER

- Curing
- Etching
- Stripping
- Cleaning
- Patterining
- Crosslinking
- Hardbaking
- Surface Treatment

- | Atomically clean semiconductor wafers (Si, Ge, GaAs), glass substrates, coverslips, thin film coated substrates.
- | Quick cleaning of SPTs, AFM, SEM and TEM samples, substrates and surfaces.
- | Quick cleaning of TEM grids, SPTs, AFM cantilevers, and other microscopy tools.
- | Cleaning and treating of Lenses and Optics.
- | Enhance adhesion of thin film coatings, thick paints and adhesives.
- | UV Curing, Etching, Patterning and Crosslinking.
- | Photoresist ashing, stripping, descum and hardbaking.
- | To alter Hydrophobic surfaces more Hydrophilic and vice-versa.
- | Increased Surface Wettability of liquids.
- | cleaning of Surface Plasmon Resonance (SPR) samples.
- | Removal of fingerprint marks.
- | Cleaning MEMS devices.
- | Surface modification and activation.

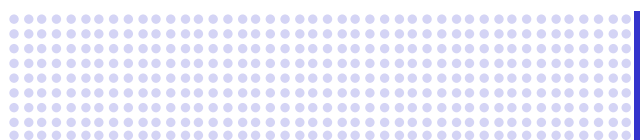


## Applications

1. Cleaning Glass and Wafers.
2. Cleaning Coated thin films (e.g. ITO Coated glass, metal oxides, semiconductor oxides).
3. Strip Photoresist.
4. Clean Production Line LCD/LED displays.
5. Clean Platinum / Gold surfaces.
6. Activate PDMS, polymers, microfluid, organic materials.
7. Crosslink Polymers and organic materials.
8. AFM cantilever, TEM grids treatment and cleaning.
9. Cleaning metals and machine parts.

## Key Features

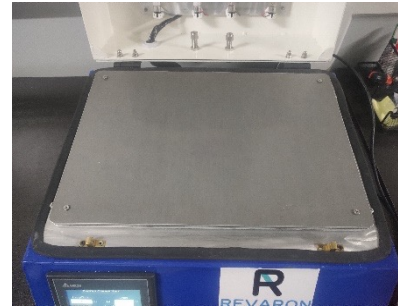
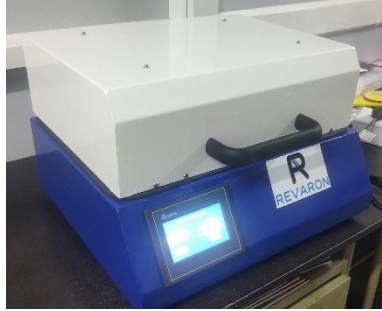
1. Bright LCD display and touch screen operation.
2. Built-in software.
3. Programmable timer, irradiance and temperature control.
4. Added Smart Safety interlocks for UV light and temperature.
5. Bench-top instrument.
6. Substrate temperature display.
7. Buzzer and light indication on completion of cleaning.
8. Enclosed UV exposure.



# Features and Specifications

- | Display  
**Colour LCD 4"**
- | UV Light Source  
**Quartz UV Grid Lamp**
- | Emission Peak Wavelengths  
**185 nm (Ozone) and 232 nm**
- | Irradiation area  
**300mm x 300mm**
- | Adjustable irradiation distance  
**5mm to 20mm**
- | UV lamp lifetime  
**Approx. 2500 hrs,  
(10 years standard use)**
- | Average light intensity at a distance of 3-5mm from the UV lamp  
**28~32 mW/cm**
- | Power Supply  
**100-240 V, 47-63 Hz,  
Fused at 5 A**
- | Continuous use time  
**1 Hour**
- | Safety features  
**Interlock for UV emission,  
Max Temperature auto  
power cut-off, Manually  
terminated by safety button,  
Drawer safety interlock**
- | Temperature Range  
**25 °C to 200 °C**
- | Programmable Timer Range  
**1s to 3600s, with countdown  
indication**
- | Air/Gas inlet/outlet  
**10mm diameter**
- | Sample loading/unloading  
**Drawer type sample stage**
- | External dimensions  
**430mm x 380mm x 320mm  
(LxWxH)**
- | Weight  
**≈ 10 Kgs**
- | Material  
**Stainless steel (resistant to  
acid and alkaline materials,  
anti-corrosion). Coated outside**
- | Additional Accessories
  - 1. Ozone neutralizer  
(to prevent ozone damage)**
  - 2. AFM Tip Holders**
  - 3. Trays for QCM and SPR  
Chips/Slides**
  - 4. Rotating Stage (FOR  
enhanced etch/treat/  
clean uniformity)**
  - 5. UV internal reflective mirrors**

"We can customise this product in accordance with your application, requirements including ergonomic design"



## Added Benefits

1. Avoid use of potentially toxic chemicals or solvents.
2. There is no need for pump (vacuum) and additional gas supply.
3. Low charging damage on substrates (common problem with plasma treatment/cleaning that involves ion bombardment).
4. No hazardous effluent (associated with wet cleaning or treatment)

## Sales and Support

Tele: **+91 7676564755**

Email: **info@revaron.com**

Address: **304/6, Shed K5 and K7, Seetharam Industrial Estate,  
Jalahalli, Bangalore 560013**

Website: **www.revaron.com**

**REVARON** products are shipped worldwide including one-year warranty as standard.

